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Damage to VUV, EUV, and X-ray Optics IV; and EUV and X-ray Optics: Synergy between Laboratory and Space III

**Libor Juha
Saša Bajt
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Editors

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Contents

xi Conference Committees

PART A Damage to VUV, EUV, and X-ray Optics IV

DAMAGE BY SHORT PULSES I

- 8777 04 **VUV-UV multiwavelength excitation process for high-quality ablation of fused silica (Invited Paper)** [8777-3]
K. Sugioka, K. Midorikawa, RIKEN (Japan)
- 8777 05 **Characterisation of EUV damage thresholds and imaging performance of Mo/Si multilayer mirrors** [8777-4]
M. Müller, Laser-Lab. Göttingen e.V. (Germany); F. Barkusky, KLA-Tencor Corp. (United States); T. Feigl, Fraunhofer-Institut für Angewandte Optik und Feinmechanik (Germany); K. Mann, Laser-Lab. Göttingen e.V. (Germany)
- 8777 06 **Responses of organic and inorganic materials to intense EUV radiation from laser-produced plasmas (Invited Paper)** [8777-5]
T. Makimura, S. Torii, Univ. of Tsukuba (Japan); D. Nakamura, A. Takahashi, T. Okada, Kyushu Univ. (Japan); H. Niino, National Institute of Advanced Industrial Science and Technology (Japan); K. Murakami, Univ. of Tsukuba (Japan)
- 8777 07 **Application of EUV optics to surface modification of materials** [8777-6]
O. Frolov, K. Kolacek, J. Straus, J. Schmidt, V. Prukner, Institute of Plasma Physics of the ASCR, v.v.i. (Czech Republic); A. Choukourov, Charles Univ. in Prague (Czech Republic)
- 8777 08 **EUV induced ablation and surface modification of poly(vinylidene fluoride) irradiated in vacuum or gaseous environment** [8777-7]
A. Bartnik, Military Univ. of Technology (Poland); W. Lisowski, J. Sobczak, Institute of Physical Chemistry, Polish Academy of Sciences (Poland); P. Wachulak, B. Budner, B. Korczyk, H. Fiedorowicz, J. Kostecki, Military Univ. of Technology (Poland)

MECHANISMS AND THEORY

- 8777 09 **Non-thermal phase transitions in semiconductors under femtosecond XUV irradiation (Invited Paper)** [8777-8]
N. A. Medvedev, Deutsches Elektronen-Synchrotron (Germany); H. O. Jeschke, Johann Wolfgang Goethe-Univ. Frankfurt am Main (Germany); B. Ziaja, Deutsches Elektronen-Synchrotron (Germany) and Institute of Nuclear Physics, Polish Academy of Sciences (Poland)
- 8777 0A **Hydrodynamics and detailed atomic physics treatment of x-ray free-electron-laser interaction with matter** [8777-9]
O. Peyrusse, Ctr. d'Etudes des Langues Indigènes d'Amérique, CNRS, Univ. Bordeaux 1, CNRS, Univ. Bordeaux 1 (France)

- 8777 0C **Global sensitivity analysis of the XUV-ABLATOR code** [8777-11]
V. Nevrlý, J. Janků, J. Dlabka, M. Vašínek, VŠB- Technical Univ. of Ostrava (Czech Republic); L. Juha, L. Vyšín, T. Burian, J. Lančok, Institute of Physics of the ASCR, v.v.i. (Czech Republic); J. Skřínský, Z. Zelinger, J. Heyrovský Institute of Physical Chemistry (Czech Republic); P. Pira, J. Wild, Charles Univ. in Prague (Czech Republic)
- 8777 0D **Mechanisms of structural changes induced by electronic excitations in solids (Invited Paper)** [8777-12]
Y. Shinozuka, Wakayama Univ. (Japan)
- 8777 0E **Theoretical investigation of scattering properties of crystal exposed to the XFEL femtosecond pulse** [8777-13]
A. Leonov, Belarusian State Univ. (Belarus); D. Ksenzov, Univ. Siegen (Germany); A. Benediktovitch, I. Feranchuk, Belarusian State Univ. (Belarus); U. Pietsch, Univ. Siegen (Germany)

DAMAGE BY ULTRASHORT PULSES II

- 8777 0F **Multiple free electron laser pulse illumination of a carbon coated silicon substrate** [8777-14]
B. Siemer, T. Hoger, M. Rutkowski, M. Menneken, Westfälische Wilhelms-Univ. Münster (Germany); S. Düsterer, Deutsches Elektronen-Synchrotron (Germany); H. Zacharias, Westfälische Wilhelms-Univ. Münster (Germany)
- 8777 0H **Results from single shot grazing incidence hard x-ray damage measurements conducted at the SACLA FEL** [8777-16]
A. Aquila, C. Ozkan, European XFEL GmbH (Germany); R. Sobierajski, Institute of Physics, Polish Academy of Science (Poland); V. Hájková, T. Burian, J. Chalupsky, L. Juha, Institute of Physics of the ASCR, v.v.i. (Czech Republic); M. Störmer, Helmholtz-Zentrum Geesthacht (Germany); H. Ohashi, Japan Synchrotron Radiation Research Institute (Japan) and RIKEN (Japan); T. Koyama, K. Tono, Japan Synchrotron Radiation Research Institute (Japan); Y. Inubushi, M. Yabashi, RIKEN (Japan); H. Sinn, T. Tschentscher, A. P. Mancuso, European XFEL GmbH (Germany); J. Gaudin, Univ. of Bordeaux (France)

DAMAGE BY ULTRASHORT PULSES III

- 8777 0I **Thermal effects on Co/Mo2C multilayer mirrors studied by soft x-ray standing wave enhanced photoemission spectroscopy** [8777-17]
A. Giglia, S. Mukherjee, Lab. Nazionale TASC, CNR, Istituto Officina dei Materiali (Italy); N. Mahne, Sincrotrone Trieste S.C.p.A. (Italy); S. Nannarone, Lab. Nazionale TASC, CNR, Istituto Officina dei Materiali (Italy) and Univ. degli Studi di Modena e Reggio Emilia (Italy); P. Jonnard, K. Le Guen, Y.-Y. Yuan, J.-M. André, Lab. de Chimie Physique-Matière et Rayonnement, CNRS, Univ. Pierre et Marie Curie (France); Z.-S. Wang, H.-C. Li, J.-T. Zhu, Tongji Univ. (China)

- 8777 OJ **Fragmentation of clusters and recombination induced by intense and ultrashort x-ray laser pulses** [8777-18]
N. Timneanu, B. Iwan, J. Andreasson, M. Bergh, M. Seibert, Uppsala Univ. (Sweden); C. Bostedt, S. Schorb, Technische Univ. Berlin (Germany) and SLAC National Accelerator Lab. (United States); H. Thomas, Technische Univ. Berlin (Germany) and The Univ. of Texas at Austin (United States); D. Rupp, T. Gorkhover, M. Adolph, T. Möller, Technische Univ. Berlin (Germany); A. Helal, K. Hoffmann, N. Kandadai, J. Keto, T. Ditmire, The Univ. of Texas at Austin (United States)

DAMAGE TO DETECTORS

- 8777 OK **Study of high-dose x-ray radiation damage of silicon sensors (Invited Paper)** [8777-19]
J. Schwandt, E. Fretwurst, R. Klanner, Univ. Hamburg (Germany); I. Pintilie, National Institute for Materials Physics (Romania); J. Zhang, Univ. Hamburg (Germany)

EXPERIMENTAL TECHNIQUES

- 8777 OM **An interferometric diagnostic for the experimental study of dynamics of solids exposed to intense and ultrashort radiation (Invited Paper)** [8777-21]
C. Fourment, F. Deneuville, B. Chimier, D. Descamps, F. Dorchies, S. Hulin, S. Petit, O. Peyrusse, J. J. Santos, Ctr. d'Etudes des Langues Indigènes d'Amérique, CNRS, Univ. Bordeaux 1 (France)
- 8777 ON **A new method of determination of ablation threshold contour in the spot of focused XUV laser beam of nanosecond duration** [8777-22]
K. Kolacek, J. Schmidt, J. Straus, O. Frolov, V. Prukner, R. Melich, Institute of Plasma Physics of the ASCR, v.v.i. (Czech Republic); A. Choukourov, Charles Univ. in Prague (Czech Republic)
- 8777 OP **RF plasma cleaning of mirror surfaces: characterization, optimization, and surface physics aspects of plasma cleaning (Invited Paper)** [8777-24]
E. Pellegrin, I. Śics, C. Pérez Sempere, J. Reyes Herrera, CELLS - ALBA (Spain); V. Carlino, ibss Group, Inc. (United States)

POSTER SESSION

- 8777 OR **Study of EUV and x-ray radiation hardness of silicon photodiodes** [8777-27]
V. V. Zabrodsky, P. N. Aruev, V. V. Filimonov, N. A. Sobolev, E. V. Sherstnev, V. P. Belik, Ioffe Physico-Technical Institute (Russian Federation); A. D. Nikolenko, D. V. Ivlyushkin, V. F. Pindyurin, N. S. Shadrin, A. E. Soldatov, M. R. Mashkovtsev, Budker Institute of Nuclear Physics (Russian Federation)
- 8777 OS **Electron kinetics in liquid water excited by a femtosecond VUV laser pulse** [8777-28]
K. Huthmacher, Technische Univ. Kaiserslautern (Germany); N. Medvedev, Deutsches Elektronen-Synchrotron (Germany); B. Rethfeld, Technische Univ. Kaiserslautern (Germany)

- 8777 OT **Characterizing the focus of a multilayer coated off-axis parabola for FLASH beam at $\lambda = 4.3$ nm** [8777-29]
A. F. G. Leontowich, Deutsches Elektronen-Synchrotron (Germany); A. Aquila, European XFEL GmbH (Germany); F. Stellato, R. Bean, H. Fleckenstein, M. Prasciolu, M. Liang, D. P. DePonte, A. Barty, F. Wang, Deutsches Elektronen-Synchrotron (Germany); J. Andreasson, J. Hajdu, Uppsala Univ. (Sweden); H. N. Chapman, Deutsches Elektronen-Synchrotron (Germany) and Univ. Hamburg (Germany); S. Bajt, Deutsches Elektronen-Synchrotron (Germany)
- 8777 OU **King's College laser plasma x-ray source design** [8777-30]
R. Alnaimi, D. Adjei, S. Alatabi, I. A. Appuhamilage, A. Michette, King's College London (United Kingdom)

PART B *EUV and X-ray Optics: Synergy between Laboratory and Space III*

ASTRONOMICAL X-RAY OPTICS

- 8777 OW **X-ray optic developments at NASA's MSFC (Invited Paper)** [8777-31]
C. Atkins, The Univ. of Alabama in Huntsville (United States); B. Ramsey, K. Kilaru, M. Gubarev, S. O'Dell, R. Elsner, D. Swartz, J. Gaskin, M. Weisskopf, NASA Marshall Space Flight Ctr. (United States)
- 8777 OX **Hybrid x-ray optical system for space astrophysics** [8777-32]
L. Pina, Czech Technical Univ. in Prague (Czech Republic); R. Hudec, Czech Technical Univ. in Prague (Czech Republic) and Astronomical Institute of the ASCR, v.v.i. (Czech Republic); V. Tichy, Czech Technical Univ. in Prague (Czech Republic); A. Inneman, D. Cerna, J. Marsik, V. Marsikova, Rigaku Innovative Technologies Europe s.r.o (Czech Republic); W. Cash, A. F. Shipley, B. R. Zeiger, T. D. Rogers, Univ. of Colorado at Boulder (United States)
- 8777 OY **Ray-tracing study of the eROSITA telescope** [8777-33]
E. Perinati, Eberhard Karls Univ. Tübingen (Germany); M. Freyberg, Max-Planck-Institut für Extraterrestrische Physik (Germany); T. Mineo, Istituto di Astrofisica Spaziale e Fisica Cosmica di Palermo (Italy); A. Santangelo, C. Tenzer, Eberhard Karls Univ. Tübingen (Germany)
- 8777 OZ **Slumping of Si wafers at high temperature** [8777-34]
M. Mika, O. Jankovsky, P. Simek, O. Lutyakov, Institute of Chemical Technology (Czech Republic); R. Havlikova, Czech Technical Univ. in Prague (Czech Republic); Z. Sofer, Institute of Chemical Technology (Czech Republic); R. Hudec, Astronomical Institute of the ASCR, v.v.i. (Czech Republic); L. Pina, Czech Technical Univ. in Prague (Czech Republic); A. Inneman, Rigaku Innovative Technologies Europe s.r.o (Czech Republic); L. Sveda, Czech Technical Univ. in Prague (Czech Republic); V. Marsikova, Rigaku Innovative Technologies Europe s.r.o (Czech Republic)
- 8777 10 **Simple and fast algorithm for computer simulations of reflective optical systems** [8777-35]
V. Tichý, Czech Technical Univ. in Prague (Czech Republic)

- 8777 11 **NANOX: proposed Nano-Satellite X-Ray Mission** [8777-36]
V. Tichý, Czech Technical Univ. in Prague (Czech Republic) and Univ. of Jan Evangelista Purkyně (Czech Republic); V. Šimon, R. Hudec, Astronomical Institute of the ASCR, v.v.i. (Czech Republic) and Czech Technical Univ. in Prague (Czech Republic); A. Inneman, Czech Technical Univ. in Prague (Czech Republic) and Rigaku Innovative Technologies Europe s.r.o (Czech Republic); D. N. Burrows, The Pennsylvania State Univ. (United States)

DIFFRACTIVE AND REFRACTIVE X-RAY OPTICS

- 8777 12 **Concepts for rapid tuning and switching of x-ray energies** [8777-37]
W. Jark, Sincrotrone Trieste S.C.p.A. (Italy); A. Last, Karlsruher Institut für Technologie (Germany)
- 8777 13 **The impact of novel 3D diffraction optics development** [8777-38]
A. Firsov, M. Brzhezinskaya, H. Loechel, F. Siewert, A. Erko, Helmholtz-Zentrum Berlin für Materialien und Energie GmbH (Germany)
- 8777 16 **X-ray refractive optics as a Fourier transformer for high resolution diffraction** [8777-41]
P. Ershov, European Synchrotron Radiation Facility (France) and Immanuel Kant Baltic Federal Univ. (Russian Federation); S. Kuznetsov, Institute of Microelectronics Technology (Russian Federation); I. Snigireva, European Synchrotron Radiation Facility (France); V. Yunkin, Institute of Microelectronics Technology (Russian Federation); A. Goikhman, Immanuel Kant Baltic Federal Univ. (Russian Federation); A. Snigirev, European Synchrotron Radiation Facility (France)

X-RAY MICROSCOPES AND ACTIVE X-RAY OPTICS

- 8777 17 **Adaptive x-ray optics development at AOA-Xinetics** [8777-42]
C. F. Lillie, Lillie Consulting LLC (United States); J. L. Cavaco, A. D. Brooks, K. Ezzo, Northrop Grumman AOA-Xinetics (United States); D. D. Pearson, Dynapeiron (United States); J. A. Wellman, Metenco LLC (United States)
- 8777 18 **Active x-ray optics** [8777-43]
R. Hudec, Astronomical Institute of the ASCR, v.v.i. (Czech Republic) and Czech Technical Univ. in Prague (Czech Republic); A. Inneman, Rigaku Innovative Technologies Europe s.r.o (Czech Republic); L. Pina, Czech Technical Univ. in Prague (Czech Republic); D. Černá, Rigaku Innovative Technologies Europe s.r.o (Czech Republic); V. Tichý, Czech Technical Univ. in Prague (Czech Republic)
- 8777 19 **Water-window microscopy using compact, laser-plasma source based on Ar/He double stream gas-puff target** [8777-44]
P. W. Wachulak, M. Skorupka, A. Bartnik, J. Kostecki, R. Jarocki, M. Szczurek, L. Wegrzynski, T. Fok, H. Fiedorowicz, Military Univ. of Technology (Poland)

MULTILAYER X-RAY OPTICS

- 8777 1B **Spectral filtering optimization of a measuring channel of an x-ray broadband spectrometer** [8777-46]
B. Emprin, CEA, Direction des Applications Militaires (France) and Lab. Charles Fabry, CNRS, Institut d'Optique, Univ. Paris Sud (France); P. Troussel, B. Villette, CEA, Direction des Applications Militaires (France); F. Delmotte, Lab. Charles Fabry, CNRS, Institut d'Optique, Univ. Paris Sud (France)
- 8777 1C **Single and multi-channel Al-based multilayer systems for space applications in EUV range** [8777-47]
E. Meltchakov, S. De Rossi, R. Mercier, F. Varniere, A. Jérôme, Lab. Charles Fabry, CNRS, Institut d'Optique, Univ. Paris Sud (France); F. Auchere, X. Zhang, Institut d'Astrophysique Spatiale (France); M. Roullay, Institut des Sciences Moléculaires d'Orsay (France); F. Delmotte, Lab. Charles Fabry, CNRS, Institut d'Optique, Univ. Paris Sud (France)
- 8777 1D **Multilayer reflective polarizers for the far ultraviolet** [8777-48]
J. I. Larruquert, J. A. Aznárez, L. Rodríguez-de Marcos, J. A. Méndez, GOLD-Instituto de Óptica, Consejo Superior de Investigaciones Científicas (Spain); A. M. Malvezzi, Univ. degli Studi di Pavia (Italy); A. Giglia, CNR, Istituto Officina dei Materiali (Italy); P. Miotti, F. Frassetto, CNR, Istituto di Fotonica e Nanotecnologie (Italy); G. Massone, INAF - Osservatorio Astronomico di Torino (Italy); S. Nannarone, Univ. di Modena e Reggio Emilia (Italy); G. Crescenzo, G. Capobianco, S. Fineschi, INAF - Osservatorio Astronomico di Torino (Italy)
- 8777 1E **Narrowband coatings for the 100-105 nm range** [8777-49]
L. Rodríguez-de Marcos, J. A. Méndez, M. Vidal-Dasilva, J. A. Aznárez, J. I. Larruquert, GOLD-Instituto de Óptica, Consejo Superior de Investigaciones Científicas (Spain)
- 8777 1F **Optical performance, structure, and thermal stability of Al/Zr multilayers working at above 17nm** [8777-50]
Z. Wang, Q. Zhong, Z. Zhang, J. Zhu, Tongji Univ. (China); Y. Bai, Changchun Institute of Optics, Fine Mechanics and Physics (China); P. Jonnard, K. Le Guen, J.-M. Andre, Lab. de Chimie Physique-Matière et Rayonnement, CNRS, Univ. Pierre et Marie Curie (France)

COHERENT RADIATION/LASERS

- 8777 1H **EUV optics in photoionization experiments (Invited Paper)** [8777-53]
A. Bartnik, P. Wachulak, H. Fiedorowicz, T. Fok, R. Jarocki, J. Kostecki, A. Szczurek, M. Szczurek, Military Univ. of Technology (Poland); L. Pina, L. Sveda, Czech Technical Univ. in Prague (Czech Republic)

X-RAY HOLOGRAPHY AND INTEGRATED DEVICES AND SYSTEMS

- 8777 1J **A novel monochromator for ultrashort soft x-ray pulses** [8777-55]
M. Brzhezinskaya, A. Firsov, K. Holldack, T. Kachel, R. Mitzner, N. Pontius, C. Stamm, J.-S. Schmidt, A. Föhlisch, A. Erko, Helmholtz-Zentrum Berlin für Materialien und Energie GmbH (Germany)

- 8777 1K **4H-SiC and novel Si GaAs-based M-S-M radiation hard photodetectors applicable in UV, EUV, and soft x-ray detection: design, technology, and performance testing** [8777-56]
F. Dubecký, Institute of Electrical Engineering, Slovak Academy of Sciences (Slovakia);
J. Kováč, J. Kováč Jr., Slovak Univ. of Technology (Slovakia); B. Zafko, Institute of Electrical Engineering, Slovak Academy of Sciences (Slovakia); J. Oswald, P. Hubík, D. Kindl, Institute of Physics of the ASCR, v.v.i. (Czech Republic); G. Vanko, Institute of Electrical Engineering, Slovak Academy of Sciences (Slovakia); E. Gombia, C. Ferrari, CNR, Istituto Materiali per Elettronica e Magnetismo (Italy); P. Boháček, Institute of Electrical Engineering, Slovak Academy of Sciences (Slovakia); A. Šagátová, V. Nečas, Slovak Univ. of Technology (Slovakia); M. Sekáčová, Institute of Electrical Engineering, Slovak Academy of Sciences (Slovakia)

Author Index

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Damage by Short Pulses I

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Mechanisms and Theory

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Damage by Ultrashort Pulses II

Regina Soufli, Lawrence Livermore National Laboratory
(United States)

Damage by Ultrashort Pulses III

Regina Soufli, Lawrence Livermore National Laboratory
(United States)

Damage to Detectors

Rolf Antonie Loch, CFRL in Hamburg (Germany)

Experimental Techniques

Frank Siewert, Helmholtz-Zentrum Berlin für Materialien und Energie
GmbH (Germany)

Part B EUV and X-ray Optics: Synergy between Laboratory and Space III

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X-ray Microscopes and Active X-ray Optics
Zhanshan Wang, Tongji University (China)

Multilayer X-ray Optics
František Dubecký, Institute of Electrical Engineering (Slovakia)

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